

## IN THE CLAIMS

We claim:

1. A structure comprising:
  - a first set of features disposed in the scribeline, said first set of features being a subset of product features; and
  - a second set of features disposed adjacent to said first set of features, said second set occupying a smaller area than said first set, said second set being similar to said first set, said second set being distinguishable from surrounding structures.
2. The structure of claim 1 wherein critical dimension (CD) is measured on said first set of features.
3. The structure of claim 1 wherein said first set of features and said second set of features differ in spaces between features.
4. The structure of claim 1 wherein said first set of features and said second set of features differ in linewidths of features.
5. The structure of claim 1 wherein said first set of features and said second set of features have the same pitch for features.

6. The structure of claim 1 wherein said first set of features comprises a first array of holes.
7. The structure of claim 6 wherein said first array of holes comprises a 5-by-5 square array of holes.
8. The structure of claim 6 wherein said second set of features comprises a second array of holes.
9. The structure of claim 8 wherein said second array of holes differs from said first array of holes in size of array.
10. The structure of claim 8 wherein said second array of holes differs from said first array of holes in space between holes.
11. The structure of claim 8 wherein said second array of holes differs from said first array of holes in linewidths of holes.
12. A method comprising:
  - extracting a subset from product features to form a first set of features;
  - extracting a small portion from said first set of features to form a template;

transforming said template into a second set of features by  
rotating said template;  
scaling spaces between features in said template;  
scaling linewidths of features in said template;  
merging said first set and said second set of features to form a test  
structure.

13. The method of claim 12 wherein critical dimension (CD) is measured on  
said first set of features.

14. A method comprising:

storing a reference image of a test structure, said reference image  
comprising a first set of features and a second set of features,  
said first set of features being a subset of product features,  
said second set of features disposed adjacent to said first set of  
features, said second set occupying a smaller area than said first set, said second  
set being similar to said first set, said second set being distinguishable from  
surrounding structures;  
capturing a test image of a sample, said test image having a plurality  
of portions;  
performing pattern recognition of each of said portions relative to said  
reference image;  
evaluating similarity of each of said portions to said reference image;  
determining a score for each of said portions;  
ranking said portions from highest score to lowest score; and  
determining location on said sample of said portion with highest score.

